



00862.022151.

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Masaya OGURA et al.) Examiner: H. Nguyen
Application No.: 09/811,419) Group Art Unit: 2851
Filed: March 20, 2001) Confirmation No.: 9530
For: EXPOSURE APPARATUS, METHOD OF) December 10, 2003
MANUFACTURING SEMICONDUCTOR :
DEVICES AND PLANT THEREFOR)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

Further to the Information Disclosure Statement filed on June 25, 2001, in compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the document listed on the enclosed PTO-1449 form. Copies of the listed documents are also enclosed.

Japanese patent document number 4-304111 shows an arrangement for adjusting correctly a projection scaling factor and a distortion of a pattern image projected by a projection optics system based on a pattern drawn on a first object, such as a reticle or a mask, by moving at least one lens system disposed in the projection optics system along the optical axis, and/or relatively moving the first object and the projection optics system along the optical axis, and changing the oscillation wavelength of light flux emitted from an illumination system. This document further discusses that even if an error is generated by a variation in the projection scaling factor of the pattern image or distortion according to

circumstances such as changes in atmospheric pressure or temperature of the projection optics system, the projection exposure apparatus makes it possible to correct the error of the projection scaling factor and the error of the distortion appropriately.

Japanese patent document number 7-211612 discusses an arrangement that adjusts a position of a wafer stage based on a measurement result of atmospheric pressure.

Japanese patent document number 10-027737 discusses an alignment optics system of an exposure apparatus in which a gap in a focal position caused by a variation in atmospheric pressure is corrected. An exposure apparatus performs an alignment processing by moving a Z-stage along a Z-axis in order to correct the gap from a conjugation position of a detection surface of a CCD in atmospheric pressure variation.

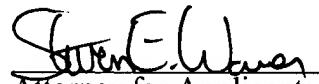
Applicants' undersigned attorney has been advised by Applicants' Japanese counsel that each of the cited documents was first discovered by the Assignee of the subject application in a search conducted at the end of September of this year, that is, not more than three months prior to the filing date of this Statement. *See* MPEP § 2001.04, page 600-128, August 2001.

Applicants request that the above information be considered by the Examiner and that a copy of the enclosed PTO-1449 form be initialed and returned indicating that such information has been considered.

No fee under 37 C.F.R. 1.97(c)(2) is believed to be due. Nevertheless, the Commissioner may charge Deposit Account No. 06-1205, should any fee be due for filing this paper.

Applicants' undersigned attorney may be reached in our Washington D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our address given below.

Respectfully submitted,



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SEW/eab

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) December 10-, 2003			ATTY DOCKET NO. 00862.022151		APPLICATION NO. 09/811,419		
			APPLICANT Masaya OGURA et al.				
			FILING DATE March 20, 2001			GROUP 2851	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	SEARCHER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
OTPE	CS	US-5,838,426	11/17/1998	Shinonaga et al.	355	52	
DEC 10 2003	TRADEMARK OFFICE	US-5,892,572	04/06/1999	Nishi	355	67	
		US-6,222,610 B1	04/24/2001	Hagiwara et al.	355	30	
		2003/0020888 A1	01/30/2003	Tanaka et al.	355	30	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
		4-30411	02/03/1992	Japan			Abstract
		7-211612	08/11/1995	Japan			Abstract
		10-27737	01/27/1998	Japan			Abstract
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER				DATE CONSIDERED			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.